

**Method for cleaning a surface of a component of a lithographic projection apparatus,
lithographic projection apparatus, device manufacturing method and cleaning system.**

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ABSTRACT

A cleaning system (100) for removing contamination (105) from at least a part of a surface (104) of a component (101) in a lithographic projection apparatus (1), comprising:
a cleaning particle provider for providing cleaning particles near said surface, which cleaning
10 particle provider comprises an electric field generator (106,V) for generating an electric field (107).
Furthermore, a method for removing contamination (105) from at least a part of a surface (104) of a component (101) of a lithographic projection apparatus (1). The method comprises generating an electric field in at least a part of the lithographic projection apparatus; providing cleaning particles near the contamination by means of said electric field (107); and removing said contamination via
15 interaction of said cleaning particles with said contamination. Thereby, contamination (105) is removed from the surface (104).

FIG. 3